Gerardo Soto

List of Publications by Year in descending order

Source: https://exaly.com/author-pdf/2865466/publications.pdf

Version: 2024-02-01

72 papers	1,404 citations	279487 23 h-index	377514 34 g-index
74 all docs	74 docs citations	74 times ranked	1618 citing authors

#	Article	IF	Citations
1	Thickness effect of Yttria-Stabilized Zirconia as the electrolyte in all-solid-state thin-film supercapacitor with a wide operating temperature range. Journal of Power Sources, 2022, 537, 231555.	4.0	6
2	Effect of inert ambient annealing on structural and defect characteristics of coaxial N-CNTs@ZnO nanotubes coated by atomic layer deposition. Ceramics International, 2022, 48, 29829-29837.	2.3	3
3	Non-quarter-wave dielectric mirror prepared by thermal atomic layer deposition. Optics and Laser Technology, 2020, 127, 106143.	2.2	1
4	YSZ thin film nanostructured battery for on-chip energy storage applications. Journal of Energy Storage, 2020, 28, 101220.	3.9	9
5	Ag nanoparticles embedded in a magnetic composite for magnetic separation applications. Journal of Alloys and Compounds, 2019, 786, 839-847.	2.8	4
6	Hot Filament Chemical Vapor Deposition of Crystalline Boron Films. Journal of the Korean Ceramic Society, 2019, 56, 269-276.	1.1	3
7	Plasma synthesis of carbon powder with embedded Fe3C nanoparticles for magnetic separation of biomolecules. Advanced Powder Technology, 2018, 29, 1035-1041.	2.0	8
8	Physical and electrical characterization of yttrium-stabilized zirconia (YSZ) thin films deposited by sputtering and atomic-layer deposition. Journal of Materials Science: Materials in Electronics, 2018, 29, 15349-15357.	1.1	14
9	Optimal sidewall functionalization for the growth of ultrathin TiO2 nanotubes via atomic layer deposition. Journal of Materials Science, 2018, 53, 2005-2015.	1.7	8
10	Low-temperature ozone treatment for carbon nanotube template removal: improving the template-based ALD method. Journal of Nanoparticle Research, 2018, 20, 1.	0.8	9
11	Fabrication of hollow TiO2 nanotubes through atomic layer deposition and MWCNT templates. Powder Technology, 2017, 308, 249-257.	2.1	31
12	Al2O3-Y2O3 ultrathin multilayer stacks grown by atomic layer deposition as perspective for optical waveguides applications. Optical Materials, 2017, 72, 788-794.	1.7	13
13	Enhancing the oxidation resistance of diamond powder by the application of Al2O3 conformal coat by atomic layer deposition. Diamond and Related Materials, 2016, 69, 108-113.	1.8	8
14	Computational and experimental study of copperâ€“gold nitride formation. Journal of Alloys and Compounds, 2015, 641, 216-222.	2.8	2
15	The control of thickness on aluminum oxide nanotubes by Atomic Layer Deposition using carbon nanotubes as removable templates. Powder Technology, 2015, 286, 602-609.	2.1	8
16	Synthesis of ReN3 Thin Films by Magnetron Sputtering. Journal of Materials, 2014, 2014, 1-9.	0.1	4
17	Structure determination and electronic structure of Cu3Au0.5N. Journal of Alloys and Compounds, 2014, 594, 48-51.	2.8	7
18	Pulsed-bed atomic layer deposition setup for powder coating. Powder Technology, 2014, 267, 201-207.	2.1	25

#	Article	IF	Citations
19	First principles calculations of interstitial and lamellar rhenium nitrides. Journal of Alloys and Compounds, 2012, 514, 127-134.	2.8	9
20	Computational study of Hf, Ta, W, Re, Ir, Os and Pt pernitrides. Computational Materials Science, 2012, 61, 1-5.	1.4	27
21	Ab initio calculations of non-stoichiometric copper nitride, pure and with palladium. Journal of Alloys and Compounds, 2011, 509, 1471-1476.	2.8	19
22	Preparation of a Ag/SiO2 nanocomposite using a fluidized bed microwave plasma reactor, and its hydrodesulphurization and Escherichia coli bactericidal activities. Powder Technology, 2011, 213, 55-62.	2.1	17
23	Evaluation of rhenium carbide as a prospective material for hard coating. Thin Solid Films, 2011, 519, 3236-3241.	0.8	5
24	Synthesis and characterization of cubic BC2N grown by reactive laser ablation. Surface and Coatings Technology, 2010, 204, 4051-4056.	2.2	30
25	Mechanical properties optimization of tungsten nitride thin films grown by reactive sputtering and laser ablation. Vacuum, 2010, 85, 69-77.	1.6	27
26	Study on the addition of nonmetal interstitial atoms to the yttrium lattice: formation of YB_x, YC_x and YN_x alloys. Physica Status Solidi (B): Basic Research, 2009, 246, 82-86.	0.7	5
27	The most probable structures of platinum nitride as a function of composition. Physica Status Solidi (B): Basic Research, 2009, 246, 1221-1224.	0.7	2
28	Electron inelastic mean free path for B4C and BC2N determined by reflection electron energy loss spectroscopy. Microelectronics Journal, 2008, 39, 1382-1384.	1.1	2
29	Stability and electronic structure of intrinsic and intercalated copper nitride alloys. Solid State Sciences, 2008, 10, 573-579.	1.5	16
30	The role of valence electron concentration in the cohesive properties of YBxN1â^'x, YCxN1â^'x and YNxO1â^'x compounds. Journal of Alloys and Compounds, 2008, 463, 559-563.	2.8	6
31	First principles study on the formation of yttrium nitride in cubic and hexagonal phases. Computational Materials Science, 2008, 42, 8-13.	1.4	26
32	Study on the formation of rhenium borides by density functional calculations. Computational Materials Science, 2008, 44, 628-634.	1.4	9
33	Electronic structure of scandium nitride with nitrogen and scandium deficits. Computational Materials Science, 2007, 40, 275-281.	1.4	29
34	Synthesis of cubic ruthenium nitride by reactive pulsed laser ablation. Journal of Physics and Chemistry of Solids, 2007, 68, 1989-1994.	1.9	57
35	Characterization of rhenium nitride films produced by reactive pulsed laser deposition. Materials Characterization, 2007, 58, 519-526.	1.9	40
36	A study on the flexibility of the hot-filament configuration and its implementation for diamond, boron carbide and ternary alloys deposition. Surface and Coatings Technology, 2006, 201, 2733-2740.	2.2	9

#	Article	IF	Citations
37	Correlation functions between specific volume and stoichiometry for transition metal nitrides. Journal of Alloys and Compounds, 2005, 389, 42-46.	2.8	10
38	Beryllium nitride: an alternative material to beryllium for extreme ultraviolet and soft X-ray uses. Optical Materials, 2004, 25, 39-42.	1.7	17
39	XPS, AES, and EELS characterization of nitrogen-containing thin films. Journal of Electron Spectroscopy and Related Phenomena, 2004, 135, 27-39.	0.8	73
40	Spectroscopic characterization of TiCx films produced by pulsed laser deposition in CH4 environments. Applied Surface Science, 2004, 230, 254-259.	3.1	21
41	AES, EELS and XPS characterization of Ti(C, N, O) films prepared by PLD using a Ti target in N2, CH4, O2 and CO as reactive gases. Applied Surface Science, 2004, 233, 115-122.	3.1	50
42	Synthesis of PtNx films by reactive laser ablation. Materials Letters, 2004, 58, 2178-2180.	1.3	20
43	Amorphous magnesium nitride films produced by reactive pulsed laser deposition. Journal of Non-Crystalline Solids, 2004, 342, 65-69.	1.5	15
44	Growth of beryllium nitride films by pulsed laser deposition; dielectric function determination. Thin Solid Films, 2003, 434, 7-13.	0.8	9
45	Tungsten nitride films grown via pulsed laser deposition studied in situ by electron spectroscopies. Applied Surface Science, 2003, 214, 58-67.	3.1	44
46	Characterization of tungsten oxide films produced by reactive pulsed laser deposition. Applied Surface Science, 2003, 218, 282-290.	3.1	28
47	Yttrium nitride thin films grown by reactive laser ablation. Journal of Physics and Chemistry of Solids, 2003, 64, 2273-2279.	1.9	54
48	Copper nitride films produced by reactive pulsed laser deposition. Materials Letters, 2003, 57, 4130-4133.	1.3	91
49	Beryllium nitride thin film grown by reactive laser ablation. Materials Letters, 2002, 52, 29-33.	1.3	45
50	Heat-Induced Polymerization of a-CNx Films Grown by Pulsed Laser Deposition. Physica Status Solidi (B): Basic Research, 2002, 230, 351-354.	0.7	0
51	Epitaxial Î±-Be3N2 thin films grown on Si substrates by reactive laser ablation. Materials Science and Engineering B: Solid-State Materials for Advanced Technology, 2002, 94, 62-65.	1.7	7
52	DLC thin films characterized by AES, XPS and EELS. Applied Surface Science, 2002, 202, 1-7.	3.1	25
53	Electron spectroscopic identification of carbon species on CNx films. Materials Letters, 2001, 49, 352-356.	1.3	11
54	Study of composition and bonding character of CNx films. Applied Surface Science, 2001, 183, 246-258.	3.1	35

#	Article	IF	Citations
55	Modification of refractive index in silicon oxynitride films during deposition. Materials Letters, 2000, 45, 47-50.	1.3	31
56	Electronic structure of Î²-Be3N2. Journal of Physics and Chemistry of Solids, 1998, 59, 743-746.	1.9	30
57	SiCxNy thin films alloys prepared by pulsed excimer laser deposition. Applied Surface Science, 1998, 127-129, 564-568.	3.1	37
58	Effects of background gasâ€“plume interaction in the deposition of SiNx films. Applied Surface Science, 1998, 127-129, 1005-1010.	3.1	13
59	In situellipsometric characterization of SiNx films grown by laser ablation. Journal of Applied Physics, 1998, 84, 5296-5305.	1.1	22
60	Growth of SiC and SiCxNy films by pulsed laser ablation of SiC in Ar and N2 environments. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1998, 16, 1311-1315.	0.9	55
61	In situ monitoring and characterization of SiC interface formed in carbon films grown by pulsed laser deposition. Journal of Vacuum Science and Technology A: Vacuum, Surfaces and Films, 1997, 15, 2585-2591.	0.9	13
62	Blue Photoluminescence from CeCl2 Doped Al2â€‰Oâ€‰3 Films. Journal of the Electrochemical Society, 1994, 141, 2860-2863.	1.3	22
63	Optical properties of boron nitride thin films. Diamond and Related Materials, 1994, 3, 831-835.	1.8	8
64	Structural Properties of Low Temperature Silicon Oxide Films Prepared by Remote Plasmaâ€Enhanced Chemical Vapor Deposition. Journal of the Electrochemical Society, 1993, 140, 3014-3018.	1.3	9
65	Luminescent Characteristics of Tb Doped Al2â€‰Oâ€‰3 Films Deposited by Spray Pyrolysis. Journal of the Electrochemical Society, 1992, 139, 267-271.	1.3	26
66	SiO2 prepared by remote plasma-enhanced chemical vapor deposition using SiCl4 and O2 at substrate temperatures of less than 200 Â°C. Thin Solid Films, 1991, 206, 6-10.	0.8	11
67	Nuclear reactions as a probe of fluorine content in SnO2:F thin films. Thin Solid Films, 1991, 203, 195-201.	0.8	17
68	Variable Energy Gap in Oxygenated Amorphous Cadmium Telluride. Japanese Journal of Applied Physics, 1991, 30, L1715-L1717.	0.8	24
69	CdTe and CdMTe (M = Fe, In, Sb) thin film studies by MÃ¶ssbauer spectroscopy and other techniques. Thin Solid Films, 1990, 193-194, 382-394.	0.8	7
70	Plasma enhanced chemical vapor deposition of SiO2 films at low temperatures using SiCl4 and O2. Journal of Electronic Materials, 1990, 19, 1411-1415.	1.0	15
71	Chemical reactivity characteristics of low-temperature chlorine-doped tin oxide deposited on hydrogenated amorphous silicon. Solar Energy Materials and Solar Cells, 1990, 20, 381-386.	0.4	2
72	Electron stimulated desorption study of irradiated poly(vinyl chloride). Applied Surface Science, 1988, 35, 213-218.	3.1	9